

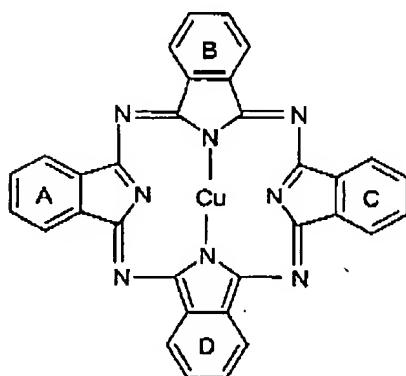
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IN THE CLAIMS

The text of all claims under examination is submitted, and the status of each is identified. This listing of claims replaces all prior versions, and listings, of claims in the application.

1. (previously presented): A photosensitive resin composition comprising as a component (A) a green colorant of the formula



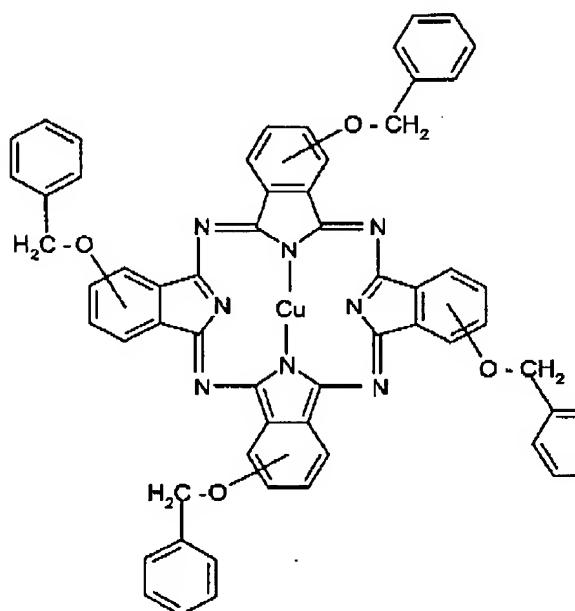
(1)

in which the rings A, B, C and D are substituted by hydroxy or by the moiety $-O-(CR_1R_2)_n-$

wherein R_1 is hydrogen or C_1-C_4 -Alkyl, R_2 is hydrogen or C_1-C_4 -Alkyl, n is 0, 1, 2 or 3 and the ring E is unsubstituted or substituted by C_1-C_6 alkyl, C_1-C_6 alkoxy, hydroxy, $NHCOR_3$, $NHSO_2R_4$ or SO_2NHR_5 , wherein R_3 is C_1-C_4 -Alkyl or phenyl, R_4 is C_1-C_4 -Alkyl or phenyl and R_5 is C_1-C_4 -Alkyl or phenyl,

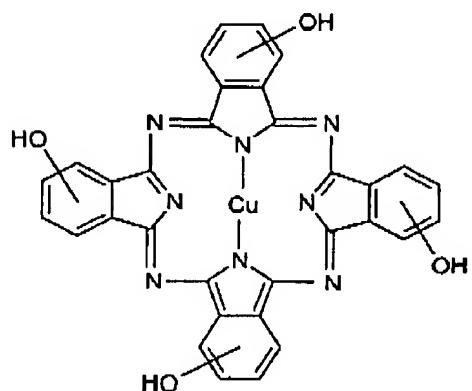
- b) as a component (B) an alkali soluble reactive or unreactive oligomer or reactive or unreactive polymer,
- c) as a component (C) a polymerizable monomer,
- d) as a component (D) a photoinitiator,
- e) as a component (E) an epoxy compound,
- and also, if desired,
- f) as a component (F) further additives.

2. (original): A photosensitive resin composition according to claim 1, wherein the component (A) is the colorant of formula



(2).

3. (original): A photosensitive resin composition according to claim 1, wherein the component (A) is the colorant of formula



(3).

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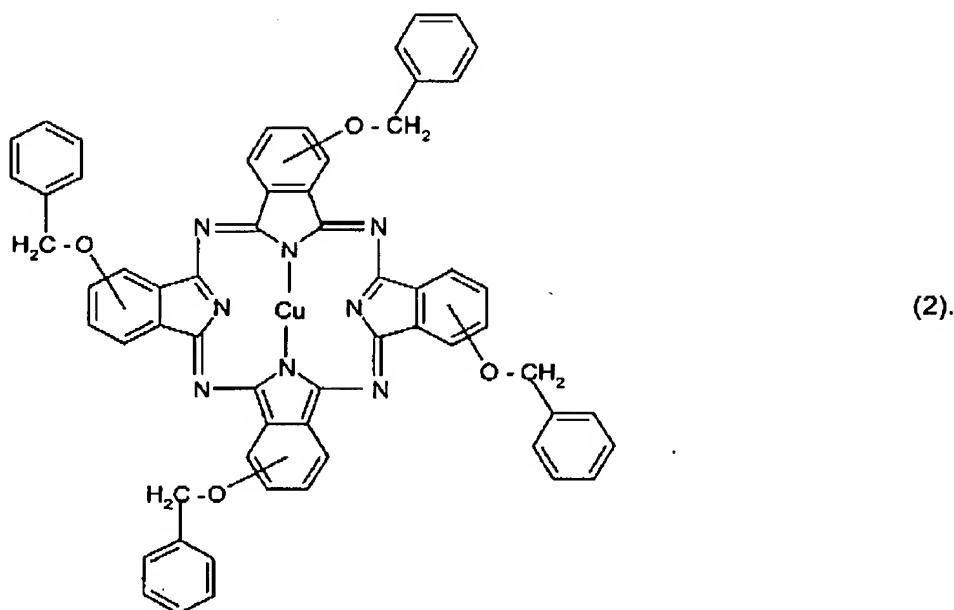
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4. (withdrawn): Solder resist process, which process comprises the steps of
(1) mixing the components (A) to (E) and if desired (F) according to claim 1,
(2) applying the resulting composition to the substrate to generate a coated substrate,
(3) evaporating the solvent, if present, at a temperature between 80-90°C,
(4) exposing the coated substrate to irradiation through a negative mask or by a direct laser imaging,
(5) developing the irradiated sample by washing with aqueous alkaline solution and thereby removing
the uncured areas,
and
(6) thermally curing the sample at a temperature about 150°C, thereby initiating the crosslinking
between the carboxylic acid and the epoxy component.

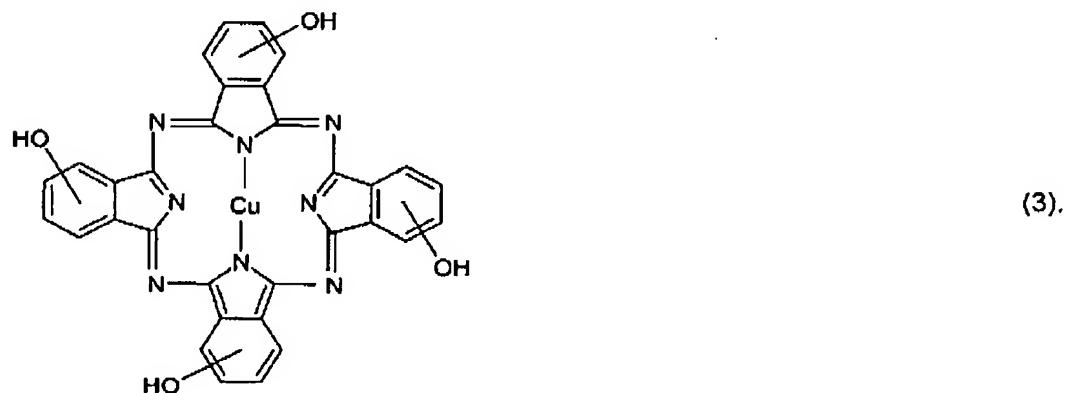
5. (withdrawn): Coated substrate obtained by the process according to claim 4.

6. (previously presented): Substrate coated with the photosensitive resin composition according to
claim 1.

7. (withdrawn): Solder resist process according to claim 4, wherein component (A) of step (1) is the
colorant of formula



8. (withdrawn): Solder resist process according to claim 4, wherein component (A) of step (1) is the colorant of formula



9. (withdrawn): Coated substrate obtained by the process according to claim 7.

10. (withdrawn): Coated substrate obtained by the process according to claim 8.

11. (previously presented): Substrate coated with the photosensitive resin composition according to claim 2.

12. (previously presented): Substrate coated with the photosensitive resin composition according to claim 3.

13. (new): A photosensitive resin according to claim 1, wherein the polymerizable monomer is a vinyl monomer.